

# Different conduction mechanisms

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# Conduction mechanisms

- Ohmic conduction ( $j = n\mu E$ )
- Thermoemission
- Schottky emission
- Direct tunneling
- Space charge limited current
- Hopping conduction

# Thermoemission

- Kinetic energy

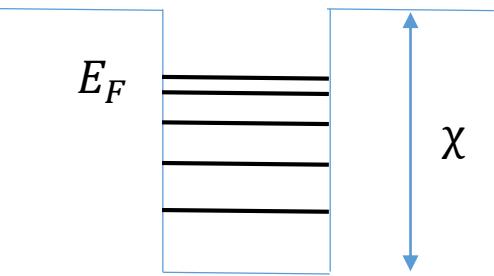
$$E(k) = \frac{1}{2}mv^2, v(k) = \frac{\hbar k}{m}$$

- Electron density

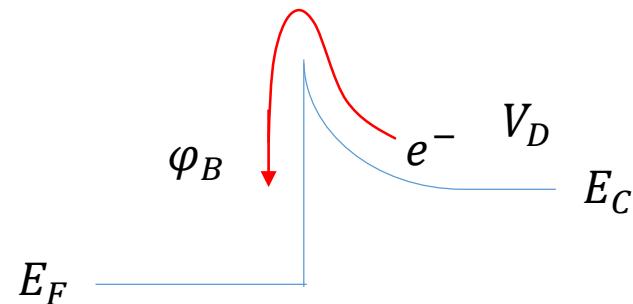
$$dn = 2\left(\frac{m}{2\pi\hbar}\right)^3 \exp\left(-\frac{\frac{1}{2}mv^2 - E_F}{k_B T}\right) dv$$

- Current density

$$\begin{aligned} j &= -qvn \\ &= 2\left(\frac{m}{2\pi\hbar}\right)^3 \exp\left(\frac{E_F}{k_B T}\right) \int_{-\infty}^{\infty} d\nu_x \int_{-\infty}^{\infty} d\nu_y \int_{\chi-E_F}^{\infty} (-qv_z) \exp\left(-\frac{\frac{1}{2}mv^2}{k_B T}\right) d\nu_z \\ &= -\frac{4\pi mq(k_B T)^2}{h^3} \exp\left(-\frac{\chi - E_F}{k_B T}\right) \end{aligned}$$



# Schottky emission

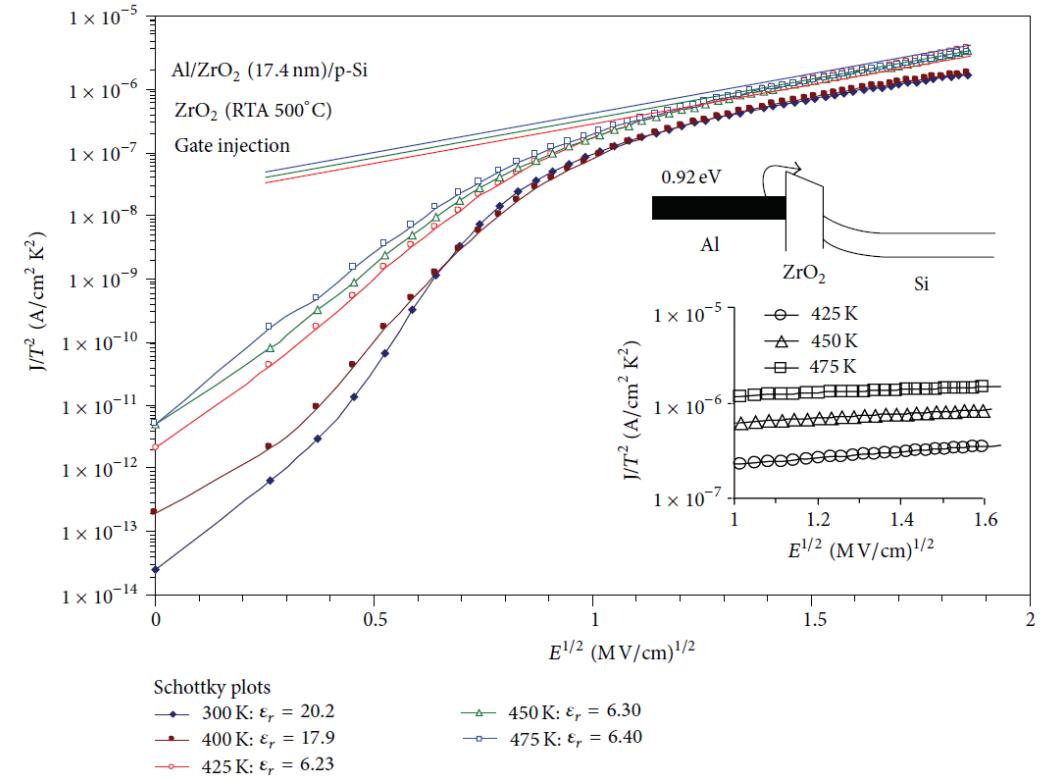


$$dn = \frac{(2m)^{3/2}}{2\pi^2 \hbar^3} \sqrt{E - E_C} \exp\left(-\frac{E - E_F}{k_B T}\right) dE = 4\pi n_0 \left(\frac{m}{2\pi k_B T}\right)^{3/2} v^2 \exp\left(-\frac{mv^2}{2k_B T}\right) dv,$$

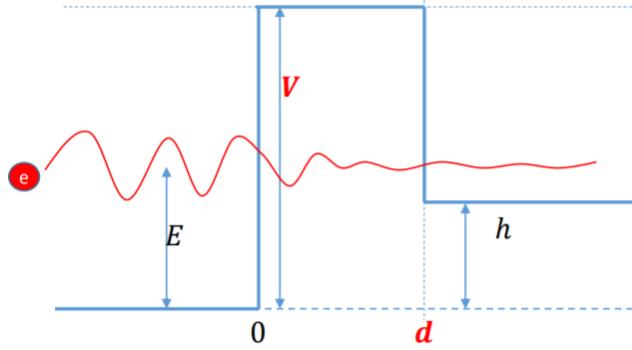
$$n_0 = N_C \exp\left(-\frac{E_C - E_F}{k_B T}\right)$$

$$j = q n_0 \left(\frac{m}{2\pi k_B T}\right)^{3/2} \int dy \int dz \int_{v_{x0}}^{\infty} v_x \exp\left(-\frac{v_x^2 + v_y^2 + v_z^2}{2k_B T}\right) dv_x = AT^2 \exp\left(-\frac{q\varphi_B}{k_B T}\right) \exp\left(\frac{qV}{k_B T}\right)$$

$$A = \frac{qm k_B^2}{2\pi^2 \hbar^3}, v_{x0} = \sqrt{\frac{-2q(V_D + V)}{m}}$$



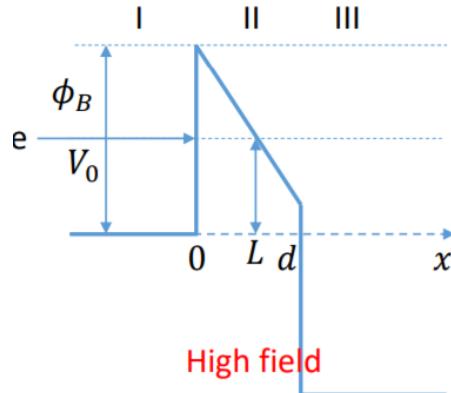
# Direct tunneling



$$T = |t|^2 = \frac{4(kk')^2}{k'^2(k + k'')^2 \cosh^2(k'd) + (kk'' - k'^2)^2 \sinh^2(k'd)}$$

Electric field

$$V(x) = V_0 - \varepsilon x$$



High field

$$I \propto T \propto e^{-2 \int k' dx}, k' = \sqrt{2m(V - E)}$$

$$I \propto e^{-\frac{4\sqrt{2me}(\Phi_B^{2/3})}{3\hbar \varepsilon}}$$

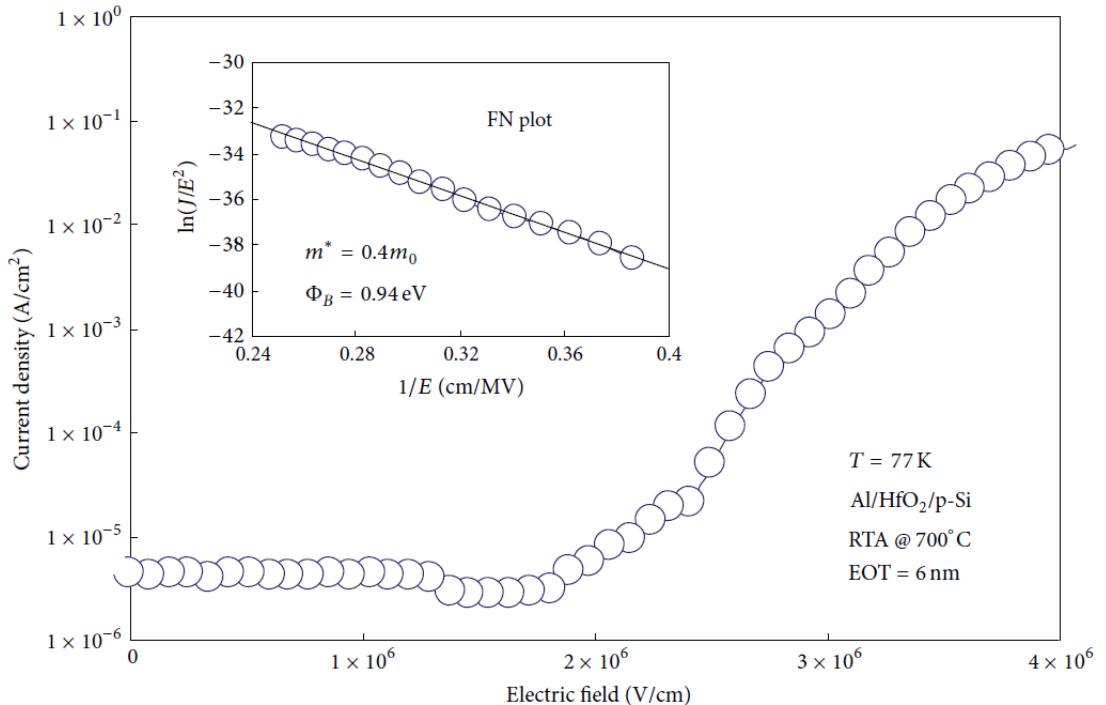
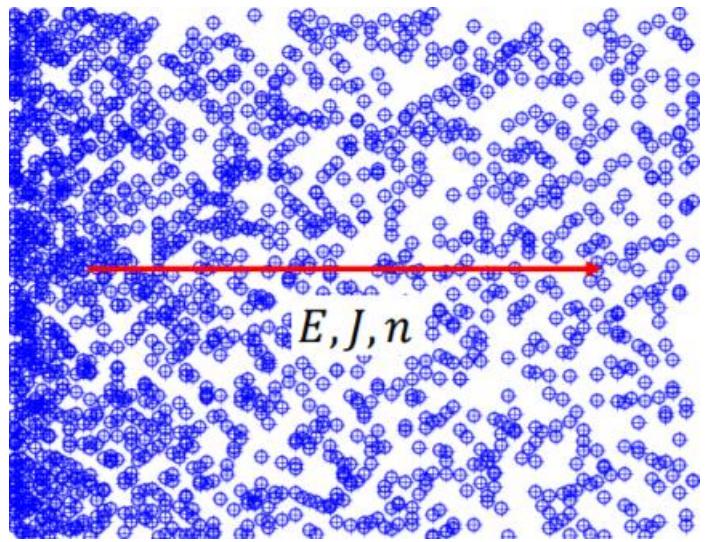


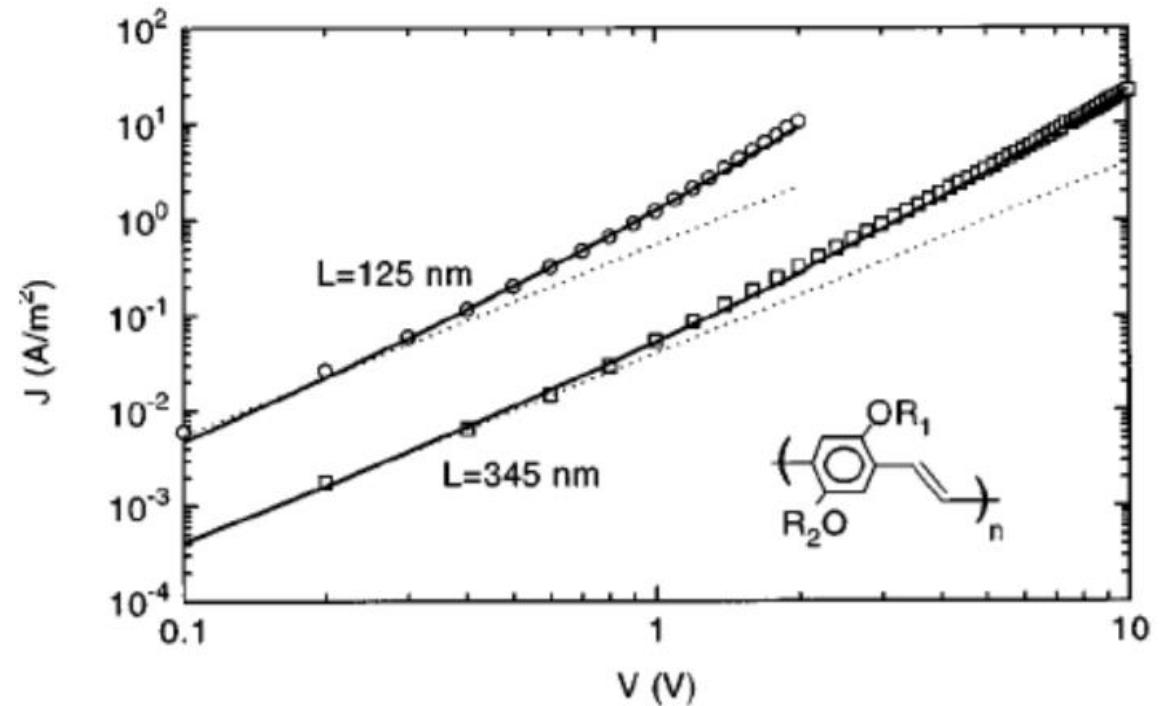
FIGURE 6: Characteristics of  $J$ - $E$  plots for  $\text{HfO}_2$  MIS capacitor at 77 K. The inset graph presents the Fowler-Nordheim tunneling.

D. K. Schroder, *Semiconductor Material and Device Characterization* edition, John Wiley & Sons, New York, NY, USA, 2<sup>nd</sup> edition, 1998

# Space charge limited current



$$\frac{J = n\mu E}{\frac{\varepsilon}{-e} \frac{dE}{dx} = n} \rightarrow n = \sqrt{\frac{\varepsilon J}{2\mu x}} \rightarrow J = \frac{9}{8} \varepsilon \mu \frac{V^2}{x^3}$$



# Hopping conduction

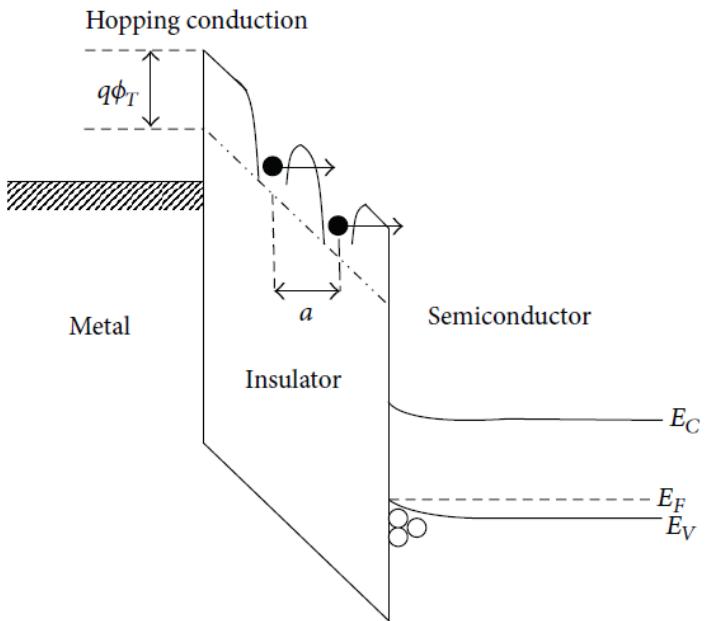


FIGURE 15: Energy band diagram of hopping conduction in metal-insulator-semiconductor structure.

$$J = qanv \exp \left[ \frac{qaE}{kT} - \frac{E_a}{kT} \right],$$

$a$  is mean hopping distance,  $n$  is electron concentration in conduction band,  $v$  is thermal vibration frequency at trap site,  $E_a$  is activation energy

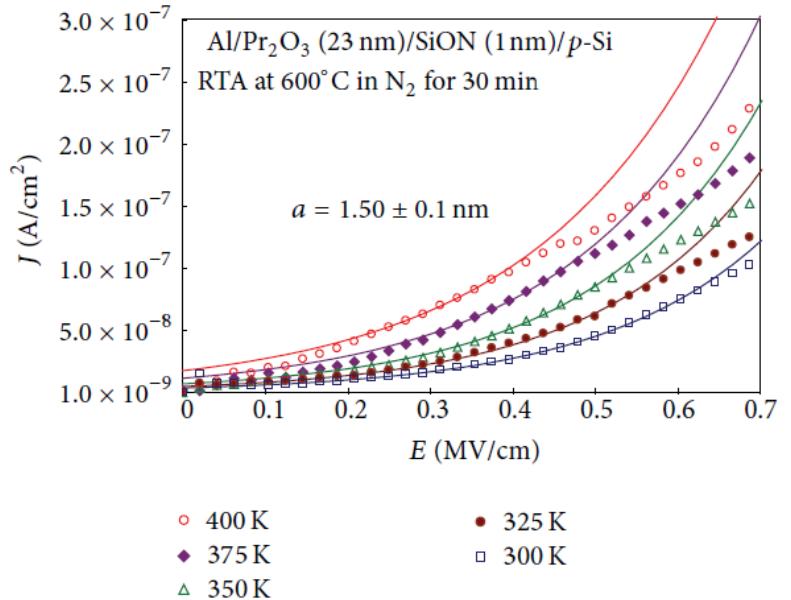


FIGURE 16:  $J$ - $E$  characteristics and simulation of hopping conduction for a laminated  $\text{Pr}_2\text{O}_3/\text{SiON}$  MIS capacitors at low electric fields.

F.-C. Chiu, C.-Y. Lee, and T.-M. Pan, *Journal of Applied Physics*, vol. 105, no. 7, 074103, 2009

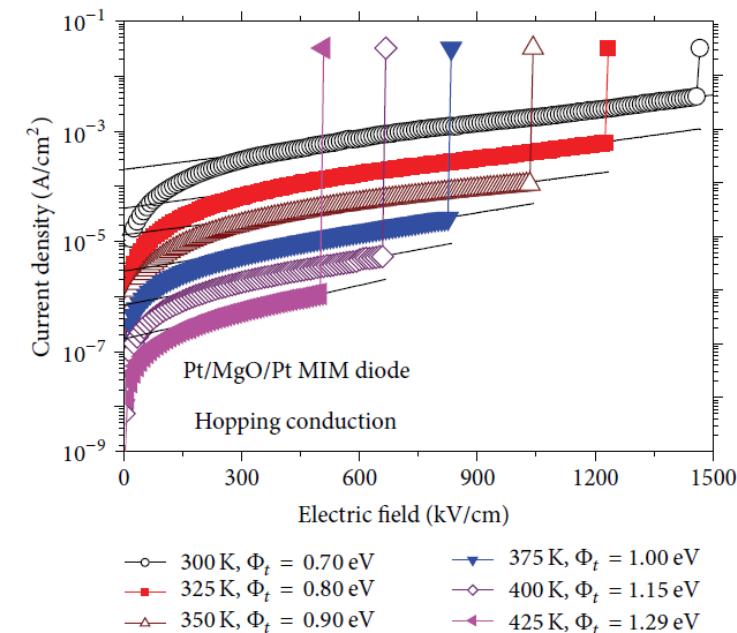


FIGURE 18: Experimental data and simulation curves of hopping conduction in high resistance state in Pt/MgO/Pt memory device.

F. C. Chiu, W. C. Shih, and J. J. Feng, *Journal of Applied Physics*, vol. 111, no. 9, 094104, 2012